

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant(s): TANABE, et al.  
Application No. TBD  
Filed: February 10, 2004  
For: METHOD FOR FABRICATING SEMICONDUCTOR  
INTEGRATED CIRCUIT DEVICE  
Expected Group: 2829  
Expected Examiner: L. Kilday

**INFORMATION DISCLOSURE STATEMENT**  
**UNDER 37 CFR 1.97 AND 1.98**

Mail Stop Patent Application  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

February 10, 2004

Sir:

Pursuant to Applicants' duty of disclosure, enclosed please find a List, on a form substantially equivalent to Form PTO-1449, of documents cited in connection with prior applications of the above-identified application, that is, in connection with at least one of Application No. 10/424,105, filed April 28, 2003; Application No. 09/939,600, filed August 28, 2001; Application No. 09/494,036, filed January 31, 2000; and Application No. 09/380,646, filed September 7, 1999.

Since each of No. 10/424,105, No. 09/939,600, No. 09/494,036 and No. 09/380,646 is being relied upon in the above-identified application under 35 USC 120, copies of the listed documents are not enclosed. See 37 CFR 1.98(d).

This Information Disclosure Statement is being submitted concurrently with the filing of the above-identified application. Accordingly, requirements of 37 CFR 1.97(b) are clearly satisfied.

Further pursuant to Applicants' duty of disclosure, the following comments are submitted in connection with technologically related subject matter:

- (1) The above-identified application and at least Serial Nos. 10/424,105, 09/494,036, 09/752,736, 09/752,766 and 09/752,737 claim priority under 35 USC 120 on application Serial No. 09/380,646, and are related to gate insulation film formation;
- (2) Application Serial No. 09/086,568 is directed to polymetal gate selective oxidation;
- (3) Application Serial No. 09/089,398, now U.S. Patent No. 6,066,508, and Continuing applications thereof (Serial No. 09/551,551, now U.S. Patent No. 6,319,860; Serial No. 09/982,173, now U.S. Patent No. 6,521,550; and Serial No. 10/013,729, now U.S. Patent No. 6,602,808) are directed to exhaust gas treatment;
- (4) Application Serial No. 09/314,956, now U.S. Patent No. 6,323,115 is directed to dual gate selective oxidation;
- (5) Application Serial No. 09/577,671, and a Continuation application thereof (Serial No. 09/635,270, now U.S. Patent No. 6,593,229) are directed to non-silicon oxide gate insulation;
- (6) Japanese Patent Application No. 09-050781, which has been laid-open as JP Laid-Open No. H09-172011 (June 30, 1997), is directed to insulation film formation; and
- (7) PCT/JP97/00188, published as WO97/28085 (August 7, 1997), is directed to water vapor generation.

In view of all of the foregoing, it is respectfully submitted that all applicable requirements of 37 CFR 1.97 and 1.98 have been satisfied, in connection with all documents on the enclosed List. Accordingly, consideration of the listed documents, upon examination of the above-identified application, is respectfully requested.

To the extent necessary, Applicants petition for an extension of time under 37 CFR § 1.136. Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to the Deposit Account No. 01-2135 (Case No. 501.37465CC8) and please credit any excess fees to such Deposit Account.

Respectfully submitted,

ANTONELLI, TERRY, STOUT & KRAUS, LLP

A handwritten signature in black ink, appearing to read "William I. Solomon", with a long horizontal flourish extending to the right.

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<b>Form PTO-1449</b>	<b>U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE</b>	<b>ATTY. DKT. NO.</b>  501.37465CC8	<b>APPLICATION NO.</b> TBD
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (Use several sheets if necessary)		<b>APPLICANT</b> TANABE, et al.	
		<b>FILING DATE</b> February 10, 2004	<b>EXPECTED GROUP</b> 2829

**U.S. PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date
AA	2001/0042344	11/22/2001	Ohmi, et al.			
AB	5,959,329	9/28/1999	Tomita, et al.			

**FOREIGN PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation/ Abstract	
						Yes	No
AC	08-213379	8/20/1996	Japan			X	
AD	11-067747	3/9/1999	Japan			X	
AE	11-074264	3/16/1999	Japan			X	
AF	10-284484	10/23/1998	Japan			X	
AG	11-162971	6/18/1999	Japan			X	
AH	11-162970	6/18/1999	Japan			X	
AI	11-204517	7/30/1999	Japan			X	
AJ	11-186255	7/9/1999	Japan			X	
AK	11-135492	5/21/1999	Japan			X	
AL	9-153489	6/10/1997	Japan			X	
AM	11-233508	8/27/1999	Japan			X	
AN	11-186248	7/9/1999	Japan			X	
AO	07-297201	11/10/1995	Japan			X	
AP	07-297181	11/10/1995	Japan			X	
AQ	07-273101	10/20/1995	Japan			X	
AS	9-148461	6/6/1997	Japan			X	

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

AR		
<b>Examiner</b>		<b>Date Considered</b>

Form PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DKT. NO.  501.37465CC8	APPLICATION NO.  TBD
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (Use several sheets if necessary)		<b>APPLICANT</b> TANABE, et al.	
		<b>FILING DATE</b> February 10, 2004	<b>EXPECTED GROUP</b> 2829

**U.S. PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date
AA	6,037,273	3/00	Gronet, et al.			
AB						
AC						
AD						
AE						
AF						
AG						
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AI						
AJ						

**FOREIGN PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation /Abstract	
						Yes	No
AM	7-86264	3/95	Japan				X
AN	7-193059	7/95	Japan			X	
AO	5-114740	5/93	Japan			X	
AP	7-321102	12/95	Japan			X	
AQ	60-107840	6/85	Japan			X	
AR	5-141871	6/93	Japan			X	
AS	5-144804	6/93	Japan			X	
AT	6-120206	4/94	Japan			X	
AU	59-132136	7/84	Japan			X	
AV	WO/9728085	7/97	PCT			X	

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

AW	
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AX	
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<b>Examiner</b>	<b>Date Considered</b>

<b>Form PTO-1449</b>	<b>U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE</b>	<b>ATTY. DKT. NO.</b>  501.37465CC9	<b>APPLICATION NO.</b>  TBD
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (Use several sheets if necessary)		<b>APPLICANT</b> TANABE, et al.	
		<b>FILING DATE</b> February 2, 2004	<b>EXPECTED GROUP</b> 2829

**U.S. PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Name	Class	Subclasses	Filing Date
AA	6,362,086	3-26-02	Weimer, et al.			
AB	5,751,025	5/98	Heminger, et al.			
AC	4,139,658	2/79	Cohen, et al.			
AD	5,693,578	12/97	Nakanishi, et al.			
AE	5,880,041	3/99	Ong			
AF	5,851,892	12/98	Lojek, et al.			
AG	5,840,368	11/98	Ohmi			
AH	5,786,263	7/98	Perera			
AI	6,239,041	5/01	Tanabe, et al.			

**FOREIGN PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Country	Class	Subclasses	Translation/Abstract	
						Yes	No
AJ	7-115069	5-2-95	Japan			X	
AK	9-172011	6/97	Japan			X	
AL	6-333918	12/94	Japan			X	
AM	7-10935	2/95	Japan				X
AN	7-115069	5/95	Japan				X
AO	5-152282	6/93	Japan			X	
AP	6-163517	6/94	Japan			X	
AQ	6-115903	4/94	Japan			X	
AR	8-111449	4/96	Japan				X

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

AS	Nakamura, et al., "Proceedings of the 45 <sup>th</sup> Symposium on Semiconductors and Integrated Circuits Technology", December 1-2, 1993. (full translation)
AT	Tanabe, et al., PG Pub: US 2002/0004315 A1, 1/10/02
AU	Tanabe, et al., PG Pub: US 2002/0019149 A1, 2/14/02
AV	Tanabe, et al., PG Pub: US 2001/0009813 A1, 7/26/01
AW	Tanabe, et al., PG Pub: US 2001/0010975 A1, 8/2/01
AX	Tanabe, et al., PG Pub: US 2001/0024870 A1, 9/27/01
AY	Tanabe, et al., PG Pub: US 2001/0006853 A1, 7/5/01
<b>Examiner</b>	
<b>Date Considered</b>	

Form PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DKT. NO. 501.37465CC8	APPLICATION NO. TBD
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (Use several sheets if necessary)		<b>APPLICANT</b> TANABE, et al.	
		<b>FILING DATE</b> February 10, 2004	<b>EXPECTED GROUP</b> 2829

**U.S. PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date
AA	4,374,116	2/15/1983	Chuang, et al.			
AB	4,119,706	10/10/1978	Rogers			
AC	3,857,927	12/31/1974	Henrie			

**FOREIGN PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation/A bstract	
						Yes	No
AD	5-19746	3/12/1993	Japan				
AE	63-85630	6/4/1988	Japan				
AF	57-49895	3/24/1982	Japan				
AG	58-19599	2/4/1983	Japan				
AH	57-82102	5/22/1982	Japan			X	
AI	55-041805	3/24/1980	Japan			X	
AJ	55-003820	1/11/1980	Japan			X	
AK	0 666 237	08/09/1995	EP				
AL	09-148315	6/6/1997	Japan			X	
AM	09-090092	4/4/1997	Japan			X	
AN							

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

AO	Japanese Patent Office Action mailed May 16, 2000 for No. 3110456 with English translation
Examiner	Date Considered

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup>Applicant's unique citation designation number (optional). <sup>2</sup>See Kinds Codes of USPTO Patent Documents at [www.uspto.gov](http://www.uspto.gov) or MPEP 901.04. <sup>3</sup>Enter Office that issued the document, by the two-letter code (WIPO Standard St.3). <sup>4</sup>For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup>Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup>Applicant is to place a check mark here if English language Translation is attached.

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